	Application No.	Applicant(s)
Notice of Allowability	10/648,554	GRUHLKE, RUSSELL W.
	Examiner	Art Unit
	William C. Choi	2873
The MAILING DATE of this communication appeal claims being allowable, PROSECUTION ON THE MERITS IS therewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this ap ) or other appropriate communication IGHTS. This application is subject to	plication. If not included n will be mailed in due course. THIS
1. $igotimes$ This communication is responsive to <u>amendment filed 3/30</u>	<u>0/2005</u> .	
2. $\boxtimes$ The allowed claim(s) is/are <u>2-6,9-14 and 24-29</u> .		
3. $igotimes$ The drawings filed on <u>25 August 2003</u> are accepted by the	e Examiner.	
4. Acknowledgment is made of a claim for foreign priority una) All b) Some* c) None of the:  1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)).  * Certified copies not received:  Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.  5. A SUBSTITUTE OATH OR DECLARATION must be submin FORMAL PATENT APPLICATION (PTO-152) which give 10 CORRECTED DRAWINGS (as "replacement sheets") must be comply including changes required by the Notice of Draftspering including changes including including changes included including changes included	e been received. e been received in Application No cuments have been received in this of this communication to file a reply MENT of this application.  nitted. Note the attached EXAMINER res reason(s) why the oath or declara st be submitted. son's Patent Drawing Review ( PTO	national stage application from the complying with the requirements  S'S AMENDMENT or NOTICE OF ation is deficient.
(b) ☐ including changes required by the attached Examiner Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1)		
each sheet. Replacement sheet(s) should be labeled as such in	the header according to 37 CFR 1.121	(d).
<ol> <li>DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT</li> </ol>		
Attachment(s)	5 🗖 N C (1 6 )	)
<ol> <li>Notice of References Cited (PTO-892)</li> <li>Dotice of Draftperson's Patent Drawing Review (PTO-948)</li> </ol>	<u>=</u>	Patent Application (PTO-152)
	6. ☐ Interview Summary Paper No./Mail Da	ite
<ol> <li>Information Disclosure Statements (PTO-1449 or PTO/SB/Paper No./Mail Date</li> </ol>		
4. Examiner's Comment Regarding Requirement for Deposit		ent of Reasons for Allowance
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Allowed Claims: 2-6, 9-14 and 24-29.

## **REASONS FOR ALLOWANCE**

The following is an examiner's statement of reasons for allowance: none of the prior art either alone or in combination disclose or teach of the claimed combination of limitations to warrant a rejection under 35 USC 102 or 103.

Specifically, with respect to independent claim 5, none of the prior art alone or in combination disclose or teach of a monolithic multi-focal length refractive element comprising a single monolithic optical element blank as claimed, specifically wherein said blank comprises first and second surface regions having respective first and second respective radii of curvature and has a maximum dimension of less than five millimeters.

Specifically, with respect to independent claim 9, none of the prior art alone or in combination disclose or teach of a method for making a multi-focal length refractive element comprising forming in an optical element blank a first surface region by etching as claimed, specifically further comprising forming on said blank a second surface region characterized by a second radius of curvature by etching using a second etch process having a second etch selectivity.

Specifically, with respect to independent claim 24, none of the prior art alone or in combination disclose or teach of a method for making a multi-focal length refractive element comprising forming in an optical element blank, first and second surface regions characterized by respective radii of curvature as claimed, specifically further comprising forming and etching a first shape transfer mask

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using a first etch process and etching said first shape transfer mask using a second etch process.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

## CONCLUSION

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Poler (U.S. 4,450,593) is being cited herein to show a method of making a refractive elements comprising etching, but does not specifically disclose wherein forming first and second surface regions of takes place in an optical element blank and wherein said regions are characterized by respective first and second radii of curvature.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to William C. Choi whose telephone number is (571) 272-2324. The examiner can normally be reached on Monday-Friday from about 9:00 am to 6 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Georgia Y. Epps can be reached on (571) 272-2328. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

William Choi Patent Examiner Art Unit 2873 May 17, 2005

Georgia Epps
Supervisory Patent Examiner
Technology Center 2800